



EUV Lithography Industrialization Progress
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This presentation will provide an overview of the industrialization of EUV Lithography, including the latest data on imaging, overlay, defectivity and source power/ productivity.

Field performance and population data of NXE:3300B and NXE:3350B systems will be shown.

Furthermore, the ASML EUV roadmap will be presented including the TWINSCAN NXE:3400B, ASML's latest EUV tool, which customers intend to use for volume production.

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